

Process data for PMMA

Resist used:

Producer: MicroChem Corp. (www.microchem.com)
Supplier: micro resist technology GmbH. (www.microresist.de)
Type: PMMA e-beam resist
Supplier order code: NANO 950 PMMA A2 (2% solid contents)
Molecular weight: 950 K
Solvent: in anisol

Pre bake: 90s at 180 deg.
Post bake: 90s at 100 deg.

Developer: 2-propanol (IPA) : 4-methyl-2 pentanon (MIBK), 3:1 (volume ratio)
developing time: 30 s (turning movement).
15s for thin layers (high resolution)

Stopper: 2-propanol (IPA), pure
stopping time: 30 s (turning movement).

Dry: with a low-nitrogen flow.

Spinning data:

